

ABSTRACT

PROCESS FOR MAKING A THIN FILM BY APPLYING PRESSURE

5 The invention relates to a process for making a thin film starting from a substrate (1) of a solid material with a plane face (2) comprising:

- the implantation of gaseous compounds in the substrate (1) to make a layer of micro-cavities (4) at a depth

10 from the said plane face (2) corresponding to the thickness of the required thin film, the gaseous compounds being implanted under conditions that could weaken the substrate at the layer of micro-cavities,

- partial or total separation of the thin film from the

15 rest of the substrate (1), this separation comprising a step in which thermal energy is added and pressure is applied to the said plane face (2).

Figure 2